

## In the Claims

Claims 1-6 (canceled).

Claim 7 (currently amended): A nickel/vanadium sputtering component structure comprising at least 99.99 weight%, excluding gases, nickel and vanadium and having an average grain size throughout the structure of less than or equal to about 40 microns.

Claim 8 (original): The nickel/vanadium sputtering component structure of claim 7 as a sputtering component pre-fab.

Claim 9 (original): The nickel/vanadium sputtering component structure of claim 7 as a sputtering component.

Claim 10 (original): The nickel/vanadium sputtering component of claim 9 wherein the average grain size is less than or equal to about 30 microns.

Claim 11 (original): The nickel/vanadium sputtering component of claim 9 wherein the average grain size is less than or equal to about 20 microns.

Claim 12 (original): The nickel/vanadium sputtering component of claim 9 comprising from about 4 weight percent vanadium to about 10 weight percent vanadium.

Claim 13 (original): The nickel/vanadium sputtering component of claim 9 comprising about 7 weight percent vanadium.

Claim 14 (original): The nickel/vanadium sputtering component of claim 9 as a sputtering target.

Claim 15 (original): A layer sputter-deposited from the sputtering target of claim 14.

Claim 16 (original): The nickel/vanadium sputtering component of claim 9 comprising at least 99.995 weight%, excluding gases, nickel and vanadium.

Claim 17 (original): The nickel/vanadium sputtering component of claim 16 wherein the average grain size is less than or equal to about 30 microns.

Claim 18 (original): The nickel/vanadium sputtering component of claim 16 wherein the average grain size is less than or equal to about 20 microns.

Claim 19 (original): The nickel/vanadium sputtering component of claim 16 comprising from about 4 weight percent vanadium to about 10 weight percent vanadium.

Claim 20 (original): The nickel/vanadium sputtering component of claim 9 comprising at least 99.999 weight%, excluding gases, nickel and vanadium.

Claim 21 (original): The nickel/vanadium sputtering component of claim 20 wherein the average grain size is less than or equal to about 30 microns.

Claim 22 (original): The nickel/vanadium sputtering component of claim 20 wherein the average grain size is less than or equal to about 20 microns.

Claim 23 (original): The nickel/vanadium sputtering component of claim 20 comprising from about 4 weight percent vanadium to about 10 weight percent vanadium.

Claims 24-39 (canceled).

Claim 40 (new) The nickel/vanadium sputtering component structure of claim 7 formed by a process which includes multiple rolling procedures that all utilize only uni-directional rolling that is along the same direction during all of the procedures.

**Claim 41 (new) The nickel/vanadium sputtering component structure of claim 7 formed by a process which includes two hot-rolling procedures and a cold-rolling procedure occurring after the two hot-rolling procedures; and wherein the hot-rolling procedures and cold-rolling procedure all utilize only uni-directional rolling that is along the same direction during all of the procedures.**